ABSTRACT OF THE DISCLOSURE

A METHOD OF MANUFACTURING A THIN FILM OF SOLID MATERIAL

The invention relates to a method of manufacturing a thin film of solid material comprising at least the following steps :

- a step of ionic implantation through one face of a substrate of said solid materials using ions capable of creating in the volume of the substrate and at a depth close to the mean depth of penetration of the ions, a layer of micro-cavities or micro-bubbles, this step being carried out at a particular temperature and for a particular length of time,
- an annealing step intended to bring the layer of micro-cavities or micro-bubbles to a particular temperature and for a particular length of time with the intention of obtaining cleavage of the substrate on both sides of the layer of micro-cavities or micro-bubbles.

The annealing step is carried out to a thermal budget made in relation to the thermal budget of the ionic implantation step and possibly other thermal budgets inferred for other steps, in order to provide said cleavage of the substrate.